

Add nitride

Silicon Substrate

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Add Poly0



Patterning through 1st level mask (Poly0) using Photolithography



Removal of Unwanted Poly0 using Reactive Ion Etching



1st Oxide Deposition using LPCVD



Patterning through 2nd level mask (Dimple) using Photolithography... and Deep RIE



Patterning through 3rd level mask (Anchor) using Photolithography and Deep RIE

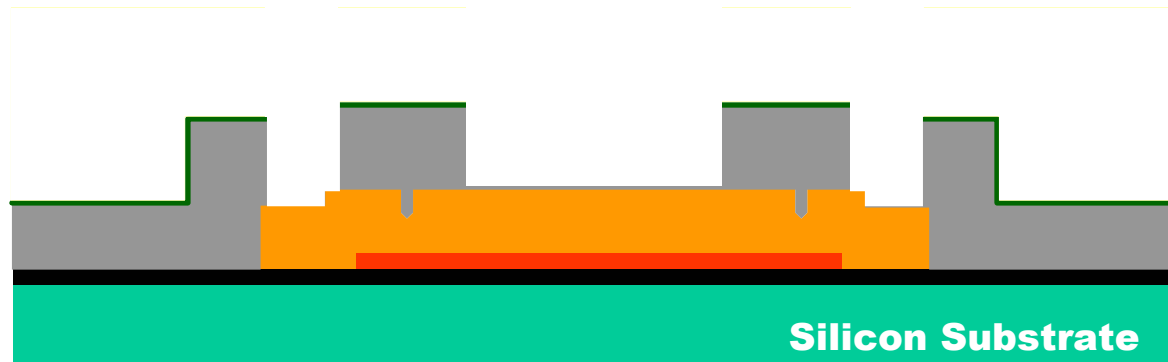


Blanket un-doped polysilicon
deposition(Poly1) using LPCVD...

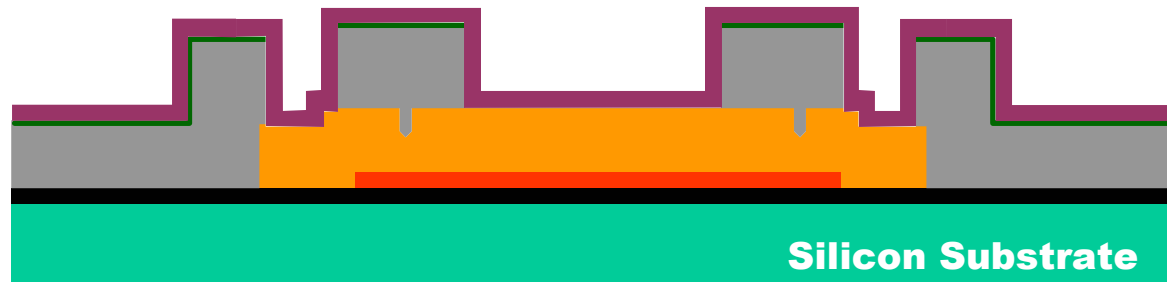
followed by PSG deposition
and annealing



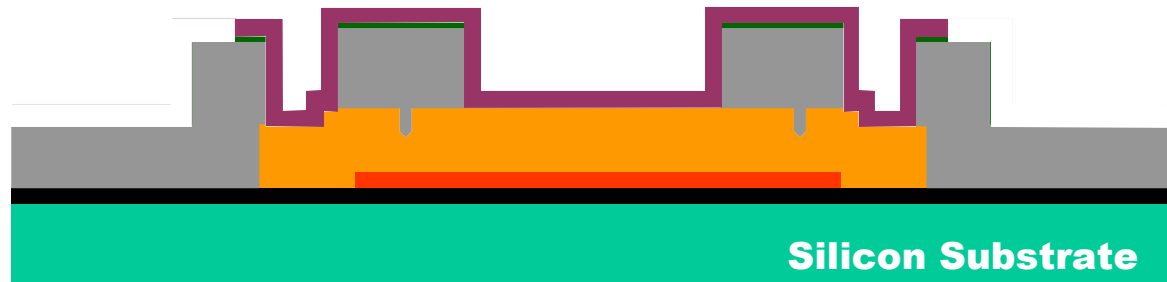
Patterning through 4th level mask (Poly1) using Photolithography... and Deep RIE



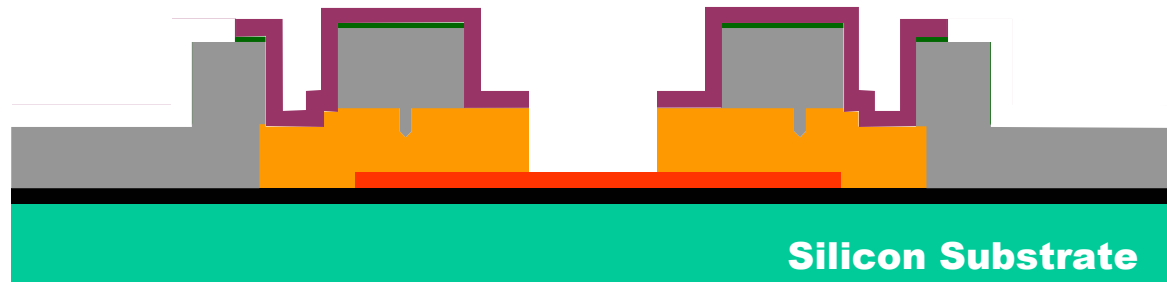
Deposition of 2nd Oxide Layer



Patterning through 5th level mask using photolithography and deep RIE

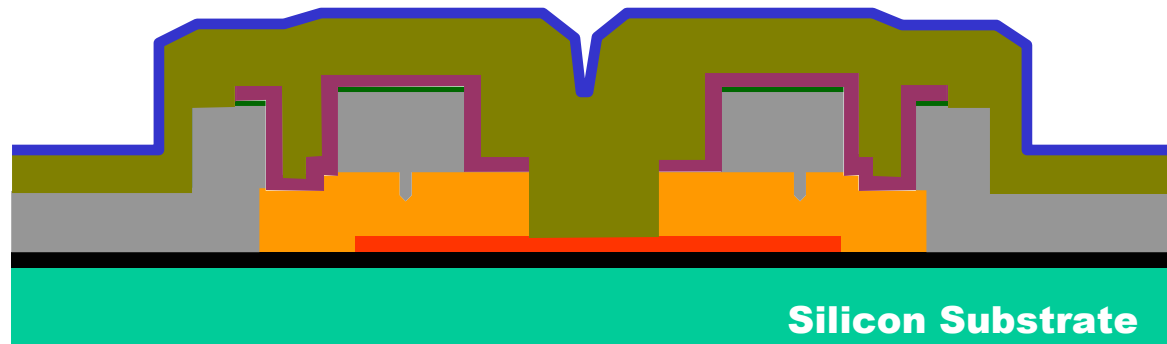


Patterning through 6th level mask using photolithography and deep RIE



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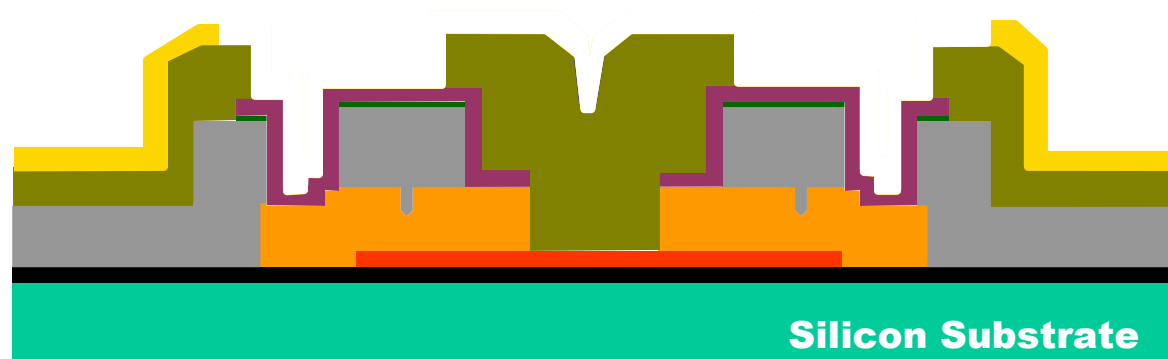
Deposition of undoped polysilicon,
followed by PSG hardmask layer,
then anneal



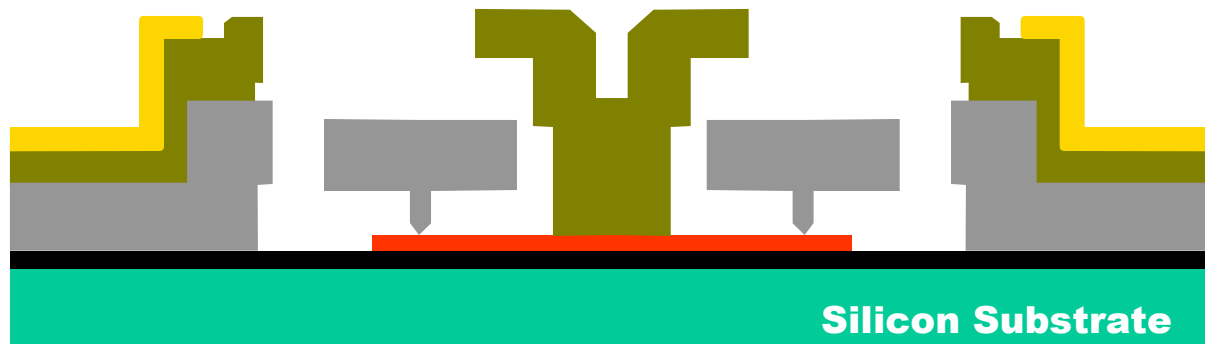
Patterning through 7th level mask using photolithography and deep RIE



Patterning through 8th level mask
using photolithography and liftoff,
followed by removal of unwanted
resist and metal in solvent bath



Release of structures using HF



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